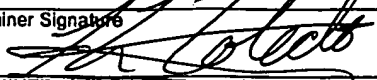


Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 12732-158001	Application No. <u>10/603949</u> New Application
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Shigeharu Monoe	
		Filing Date June 26, 2003	Group Art Unit <u>2823</u>

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
<u>LT</u>	AA	6,235,558	05/22/2001	Oda et al.			03/31/2000
<u>LT</u>	AB	US 2001/0030322 A1	10/18/2001	Yamazaki et al.			02/02/2001
<u>LT</u>	AC	US 2001/0035526 A1	11/01/2001	Yamazaki et al.			04/24/2001
<u>LT</u>	AD	US 2001/0055841 A1	12/27/2001	Yamazaki et al.			04/12/2001
<u>LT</u>	AE	US 2002/0158288 A1	10/31/2002	Yamazaki et al.			02/21/2002
	AF						
	AG						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
<u>LT</u>	AH	07-106346	04/21/1995	Japan			ABS	
<u>LT</u>	AI	08-45906	02/16/1996	Japan			ABS	
<u>LT</u>	AJ	10-10752	01/16/1998	Japan			ABS	
<u>LT</u>	AK	2000-294787	10/20/2000	Japan			ABS	
<u>LT</u>	AL	EP 1 128 430 A2	08/29/2001	Europe				
<u>LT</u>	AM	2001-313397	11/09/2001	Japan			ABS	
<u>LT</u>	AN	2002-14337	01/18/2002	Japan			ABS	

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
<u>LT</u>	AO	M. Nagase et al.; "Study of sub-30nm gate Etching Technology"; <i>2001 Dry Process International Symposium</i> ; pp. 17-22; 2001
	AP	
	AQ	
	AR	

Examiner Signature 	Date Considered <u>8/20/04</u>
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	